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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **Miwa KOZAWA et al.**

Art Unit: **1795**

Application Number: **10/720,097**

Examiner: **Daborah Chacko Davis**

Filed: **November 25, 2003**

Confirmation Number: **4454**

For: **PROCESS FOR FORMING RESIST PATTERN, SEMICONDUCTOR DEVICE
AND FABRICATION THEREOF**

Attorney Docket Number: **032132**

Customer Number: **38834**

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

June 23, 2008

Sir:

In response to the Office Action dated March 21, 2008, Applicants amend the claims as follows and submit the following remarks.

Amendments to the Claims begin on page 2 of this paper.

Remarks begin on page 8 of this paper.